

IN THE CLAIMS

Applicant notes that in the previous office action, due to a typographical error, it was erroneously indicated on page 4 of the amendment and response mailed November 12, 2002 that “the base claims (1, 14, 22, 30, and 51) have been amended.” To date in the present application, no claims have been amended.

1. (Original) A method of forming a gate oxide on a transistor body region, comprising: evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table; and oxidizing the metal layer to form a metal oxide layer on the body region.
2. (Original) The method of claim 1, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.
3. (Original) The method of claim 1, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.
4. (Original) The method of claim 3, wherein electron beam evaporation depositing the metal layer includes electron beam evaporation of a 99.9999% pure metal target material.
5. (Original) The method of claim 1, wherein evaporation depositing the metal layer includes evaporation depositing at a substrate temperature of approximately 150 - 400 °C.
6. (Original) The method of claim 1, wherein oxidizing the metal layer includes oxidizing at a temperature of approximately 400 °C.
7. (Original) The method of claim 1, wherein oxidizing the metal layer includes oxidizing with atomic oxygen.

8. (Original) The method of claim 1, wherein oxidizing the metal layer includes oxidizing using a krypton (Kr)/oxygen (O₂) mixed plasma process.
9. (Original) A method of forming a gate oxide on a transistor body region, comprising:
evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table; and
oxidizing the metal layer using a krypton(Kr)/oxygen (O₂) mixed plasma process to form a metal oxide layer on the body region.
10. (Original) The method of claim 9, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.
11. (Original) The method of claim 9, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.
12. (Original) The method of claim 11, wherein electron beam evaporation depositing the metal layer includes electron beam evaporation of a 99.9999% pure metal target material.
13. (Original) The method of claim 9, wherein evaporation depositing the metal layer includes evaporation depositing at a substrate temperature of approximately 150 - 400 °C.
14. (Original) A method of forming a transistor, comprising:
forming first and second source/drain regions;
forming a body region between the first and second source/drain regions;
evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table;
oxidizing the metal layer to form a metal oxide layer on the body region; and
coupling a gate to the metal oxide layer.

15. (Original) The method of claim 14, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.

16. (Original) The method of claim 14, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.

17. (Original) The method of claim 16, wherein electron beam evaporation depositing the metal layer includes electron beam evaporation of a 99.9999% pure metal target material.

18. (Original) The method of claim 14, wherein evaporation depositing the metal layer includes evaporation depositing at a substrate temperature of approximately 150 - 400 °C.

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19. (Original) The method of claim 14, wherein oxidizing the metal layer includes oxidizing at a temperature of approximately 400 °C.

20. (Original) The method of claim 14, wherein oxidizing the metal layer includes oxidizing with atomic oxygen.

21. (Original) The method of claim 14, wherein oxidizing the metal layer includes oxidizing using a krypton (Kr)/oxygen (O2) mixed plasma process.

22. (Original) A method of forming a memory array, comprising:
forming a number of access transistors, including:

forming first and second source/drain regions;

forming a body region between the first and second source/drain regions;

evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table;

oxidizing the metal layer to form a metal oxide layer on the body region;

coupling a gate to the metal oxide layer;


forming a number of wordlines coupled to a number of the gates of the number of access transistors;

forming a number of sourcelines coupled to a number of the first source/drain regions of the number of access transistors; and

forming a number of bitlines coupled to a number of the second source/drain regions of the number of access transistors.

23. (Original) The method of claim 22, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.

24. (Original) The method of claim 22, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.

 25. (Original) The method of claim 24, wherein electron beam evaporation depositing the metal layer includes electron beam evaporation of a 99.9999% pure metal target material.

26. (Original) The method of claim 22, wherein evaporation depositing the metal layer includes evaporation depositing at a substrate temperature of approximately 150 - 400 °C.

27. (Original) The method of claim 22, wherein oxidizing the metal layer includes oxidizing at a temperature of approximately 400 °C.

28. (Original) The method of claim 22, wherein oxidizing the metal layer includes oxidizing with atomic oxygen.

29. (Original) The method of claim 22, wherein oxidizing the metal layer includes oxidizing using a krypton (Kr)/oxygen (O2) mixed plasma process.

30. - 53. (Previously Withdrawn)

54. (Original) A transistor formed by the process, comprising:
forming a body region coupled between a first source/drain region and a second source/drain region;
evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table;
oxidizing the metal layer to form a metal oxide layer on the body region; and
coupling a gate to the metal oxide layer.
55. (Original) The transistor of claim 54, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.
56. (Original) The transistor of claim 54, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.
57. (Original) The method of claim 54, wherein oxidizing the metal layer includes oxidizing using a krypton (Kr)/oxygen (O₂) mixed plasma process.
58. (Original) A method of forming an information handling system, comprising:
forming a processor;
forming a memory array, including:
forming a number of access transistors, including:
forming first and second source/drain regions;
forming a body region between the first and second source/drain regions;
evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table;
oxidizing the metal layer to form a metal oxide layer on the body region;
coupling a gate to the metal oxide layer;

forming a number of wordlines coupled to a number of the gates of the number of access transistors;

forming a number of sourcelines coupled to a number of the first source/drain regions of the number of access transistors;

forming a number of bitlines coupled to a number of the second source/drain regions of the number of access transistors; and

forming a system bus that couples the processor to the memory array.

59. (Original) The method of claim 58, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.

60. (Original) The method of claim 58, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.

61. - 66. (Previously Withdrawn)

67. (Previously Added) A method of forming a transistor, comprising:
forming first and second source/drain regions;
forming a body region between the first and second source/drain regions;
evaporation depositing a metal layer on the body region, the metal being chosen from a group consisting of the group IIIB elements and the rare earth series of the periodic table;
oxidizing the metal layer using a krypton(Kr)/oxygen (O2) mixed plasma process to form a metal oxide layer on the body region; and
coupling a gate to the metal oxide layer.

68. (Previously Added) The method of claim 67, wherein evaporation depositing the metal layer includes depositing a metal layer, the metal layer being chosen from a group consisting of yttrium and gadolinium.

AMENDMENT AND RESPONSE UNDER 37 CFR § 1.116 – EXPEDITED PROCEDURE

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Added 69. (Previously Added) The method of claim 67, wherein evaporation depositing the metal layer includes evaporation depositing by electron beam evaporation.
